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(54) **NEGATIVE PHOTOSENSITIVE RESIN COMPOSITION AND CURED PRODUCT OF SAME**

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CPC ***G03F 7/0382*** (2013.01); ***C08G 59/063*** (2013.01); ***C08G 59/3218*** (2013.01); ***C08G 59/42*** (2013.01); ***C08L 63/00*** (2013.01); ***G03F 7/038*** (2013.01)

(58) **Field of Classification Search**

None

See application file for complete search history.

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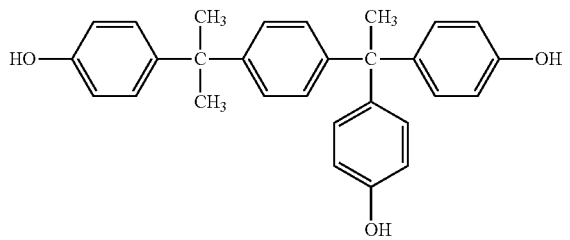
(57) **ABSTRACT**

A negative photosensitive resin composition which contains (A) an epoxy resin that has two or more epoxy groups in each molecule, (B) an alkali-soluble resin and (C) a cationic photopolymerization initiator. The epoxy resin (A) is an epoxy resin that is obtained by a reaction between a phenol derivative represented by formula (1) and an epihalohydrin.

(1)



6 Claims, No Drawings